

DRIP MANIFOLD FOR UNIFORM CHEMICAL DELIVERY

ABSTRACT OF THE DISCLOSURE

A method for cleaning a wafer with a drip nozzle being configured for use in a
5 drip manifold that is oriented over a brush of a wafer cleaning system is provided. The
drip nozzle has a first end and a second end with a passage defined there between where
the passage includes a wall that extends longitudinally between the first end and the
second end. An orifice is defined within the passage and located at the first end of the
drip nozzle. The method includes inputting a fluid into the drip nozzle at an acute angle
10 relative to a longitudinal extension of the wall and reflecting the fluid stream off an
internal wall of the drip nozzle at least twice in a direction that is toward the second end.
The method further includes outputting at least one substantially uniform drop from the
second end of the passage.